

Form PTO-1449

**INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION**

(Use several sheets if necessary)

Docket Number  
211843-00022Application Number  
10/183,768-10/748,078Applicant  
Thomas HorskyFiling Date  
June 26, 2002 12/30/04Group Art Unit  
288T 2821**U. S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
JV	6	4	5	2	3	3	8	9/17/02	Horsky	245	111.81	
JV	6	2	8	8	4	0	3	9/11/01	Horsky et al.	250	427	
JV	3	5	8	1	1	9	5	6/10/68	Robert L. Jepsen	324	470	
JV	5	5	4	3	6	2	5	8/6/96	Johnson et al.	250	427	
JV	6	3	5	2	6	2	6	3/5/02	von Zweck	204	298.04	
JV	4	7	4	0	6	9	8	4/26/88	Tamura et al.	250	310	
JV	4	2	1	7	8	5	5	8/19/80	Takagi	118	719	
JV	4	1	5	2	4	7	8	5/1/79	Takagi	428	221	
JV	3	5	5	7	3	6	5	12/22/67	Ralph Elliott Mayo Fairfield; Edward B. Delany, Ridgefield, Conn.	250	427	
JV	4	1	2	0	7	0	0	10/17/78	Morimoto	438	479	
JV	5	5	6	1	3	2	6	10/1/96	Ito et al.	257	751	
JV	5	6	8	6	7	8	9	11/11/97	Schoenbach et al.	313	491	
JV	5	5	2	8	0	3	4	6/18/96	Yamazaki et al.	250	309	
JV	4	9	4	3	7	1	8	07/90	Haines et al.	250	288	
JV	4	6	4	9	2	7	8	03/87	Chutjian et al.	250	423R	

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	Translation	
						Yes	No

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

JV	Thomas N. Horsky, Electron Beam Ion Source With Integral Low-Temperature Vaporizer, U.S. Patent Application Publication No. US 2002/0070672 A1 dated June 13, 2002
JV	Lo et al., Method and Apparatus for Multiple Charge particle Beams, U.S. Patent Application Publication No. US 2003/0001095 A1 dated January 2, 2003
JV	Brautti et al., "Trapped Ion Source", IEEE Journal 1998, pp. 2729-2731
JV	Boggia et al., "Study of a Trapped Ion Source", IEEE Journal, pp. 1433-1435

EXAMINER

DATE CONSIDERED 09/28/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.